

Amendments to the Abstract:

Please replace the Abstract on page 25 with the following:

A defect inspecting apparatus ~~[[is disclosed that]]~~ can detect finer defects with high resolution optical images of those defects, ~~and which makes the difference in contrast greater between fine line patterns of a semiconductor device.~~ The ~~[[defect inspecting]]~~ apparatus includes a sample mounting device for mounting a sample; lighting and detecting apparatus for illuminating a patterned sample mounted on a mount and detecting the optical image of the reflected light obtained therefrom. ~~[[Also included is a]]~~ A display ~~[[for displaying]]~~ displays the optical image detected by this lighting and detecting apparatus. ~~[[; an]]~~ An optical parameter setting device ~~[[for setting and displaying]]~~ sets and displays optical parameters for the lighting and detecting apparatus on the display. ~~[[; and]]~~ An optical parameter adjusting apparatus ~~[[for adjusting]]~~ adjusts optical parameters set for the lighting and detecting apparatus according to the optical parameters set by the optical parameter setting apparatus. ~~[[; a]]~~ A storage device ~~[[for storing]]~~ stores comparative image data. ~~[[; and a]]~~ A defect detecting device ~~[[for detecting]]~~ detects defects from patterns formed on the sample by comparing the optical image detected by the optical image detecting apparatus with the comparative image data stored in the storage.